

# UV PHOTONIC INTEGRATED CIRCUITS FOR LABEL-FREE STRUCTURED ILLUMINATION MICROSCOPY AND QUANTITATIVE PHASE IMAGING

Chupao Lin

Supervisors: Prof. Nicolas Le Thomas, Prof. Roel Baets

UV PHOTONIC INTEGRATED CIRCUITS FOR LABEL-FREE STRUCTURED ILLUMINATION MICROSCOPY AND QUANTITATIVE PHASE IMAGING

# WHAT IS PHOTONICS?

## Display

- LED
- TV, phones, PC
- Projectors

## Manufacturing

- Laser cutting
- UV lithography

## Communication

- Optical fiber
- Underwater

## Sensing

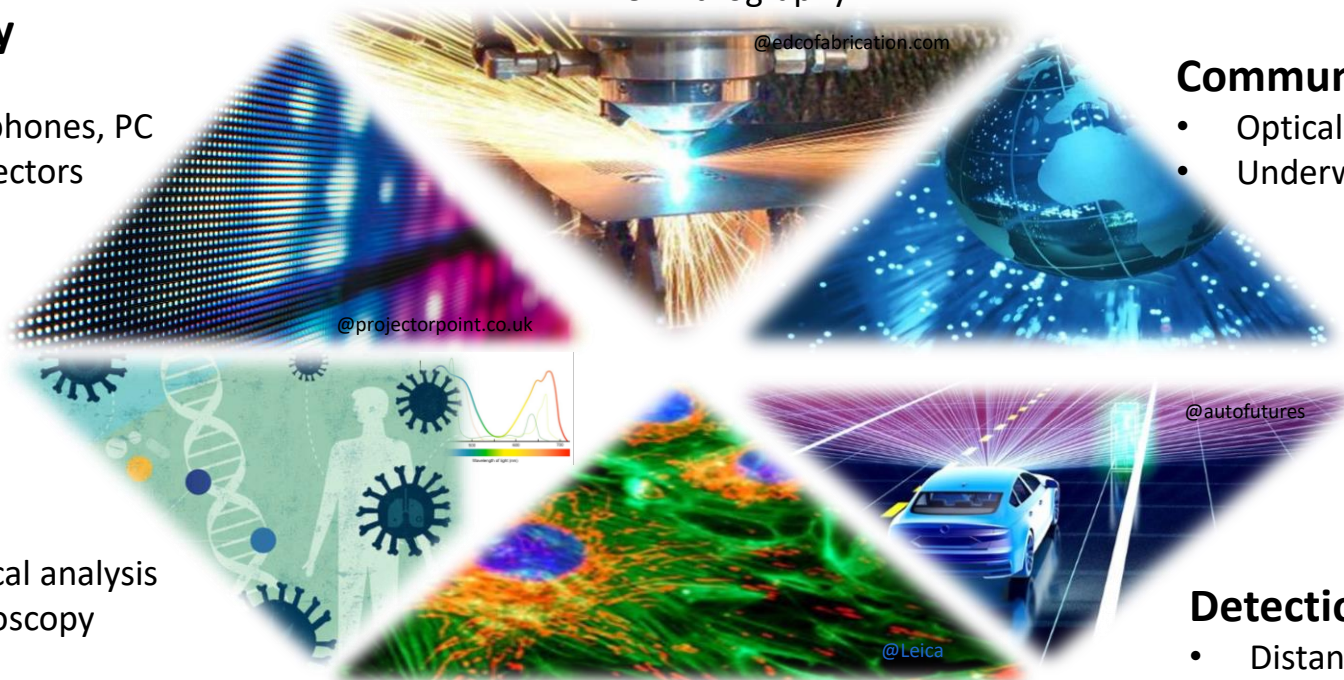
- Chemical analysis
- Spectroscopy

## Imaging

- Microscopy
- Telescope

## Detection

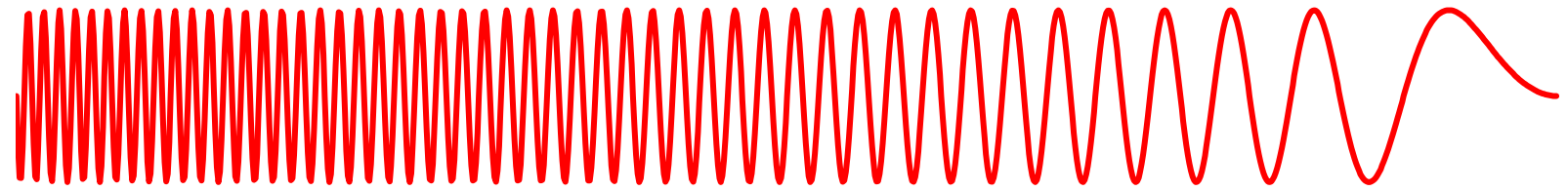
- Distance measurement
- Lidar



# WHAT IS LIGHT?

Increasing wavelength  $\lambda$   $\Rightarrow$

$$f = c/\lambda$$



$10^{19}$     $10^{16}$     $10^{14}$     $10^{14}$     $10^{12}$    Frequency  $f$  (Hz)



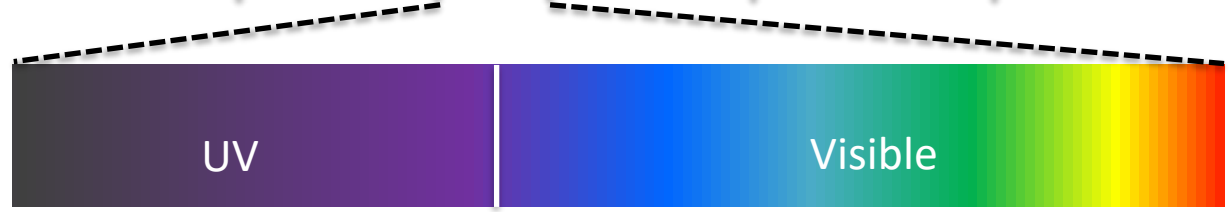
Gamma rays

X-rays

IR

Microwave

Radio frequency



UV

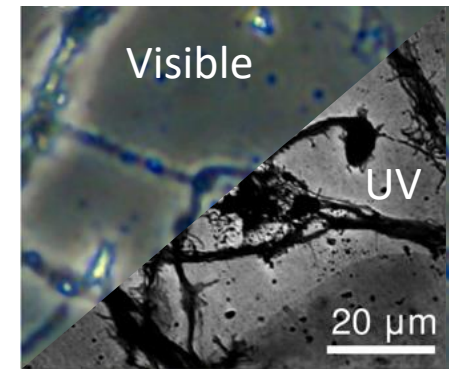
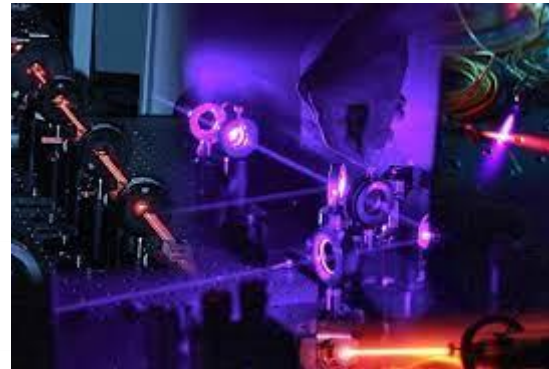
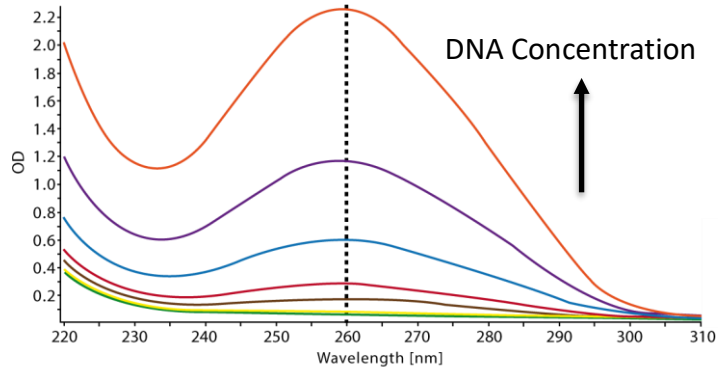
Visible

10 nm

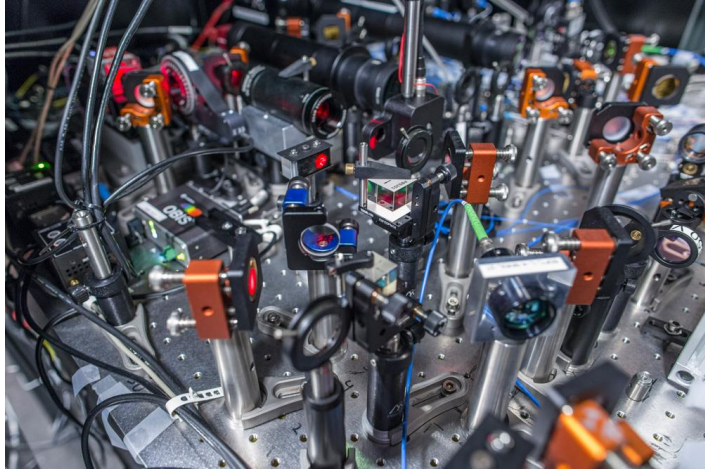
400 nm

750 nm

# WHY UV?



# COMPACT SOLUTIONS FOR UV BEAM MANIPULATION?



~m

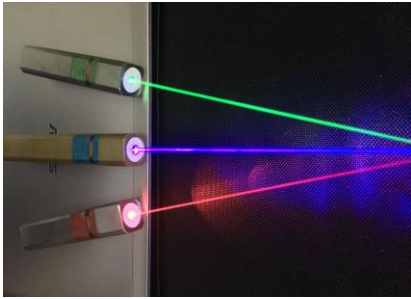


~cm

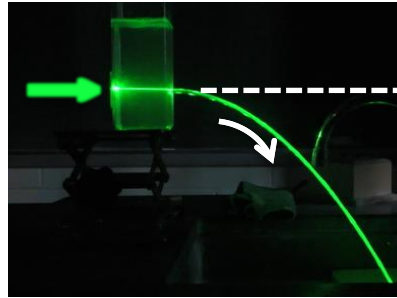
UV PHOTONIC INTEGRATED CIRCUITS FOR LABEL-FREE STRUCTURED ILLUMINATION MICROSCOPY AND QUANTITATIVE PHASE IMAGING



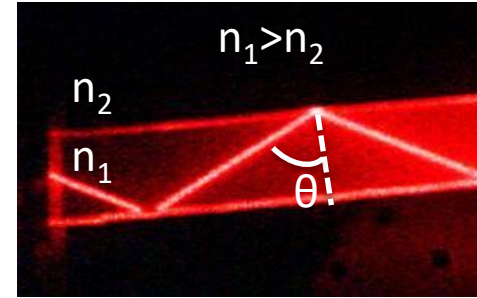
# WHAT IS PHOTONIC INTEGRATED CIRCUITS (PICs)?



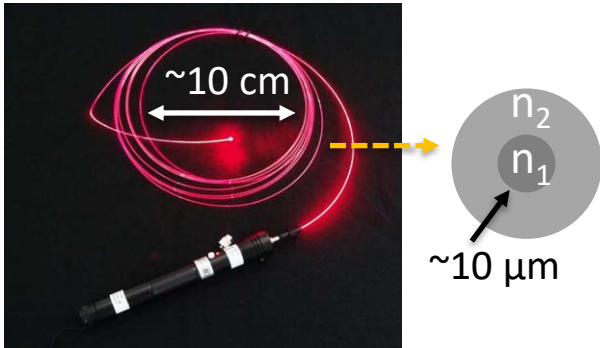
Light travels in a straight-line path



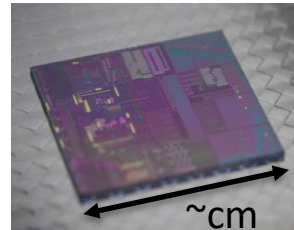
Light guided in water jet



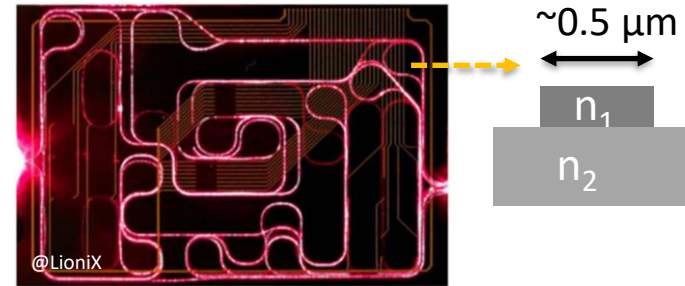
Total internal reflection



Optical fiber



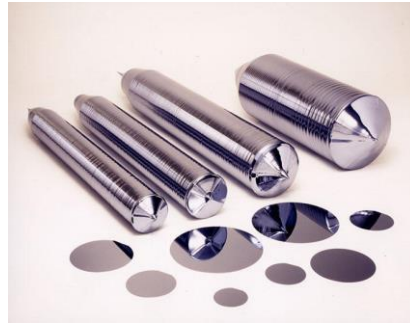
Photonic integrated circuits





# ADVANTAGES OF PHOTONIC INTEGRATED CIRCUITS

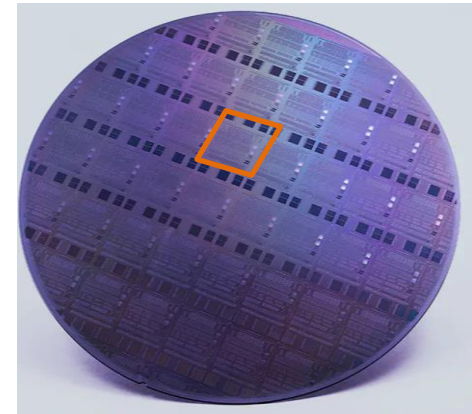
➤ Low-cost



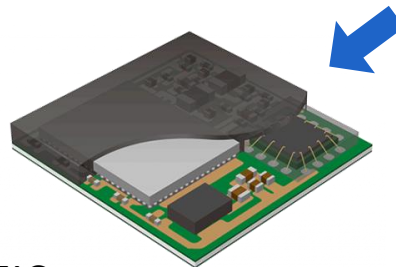
➤ Large scale fabrication



➤ Compact

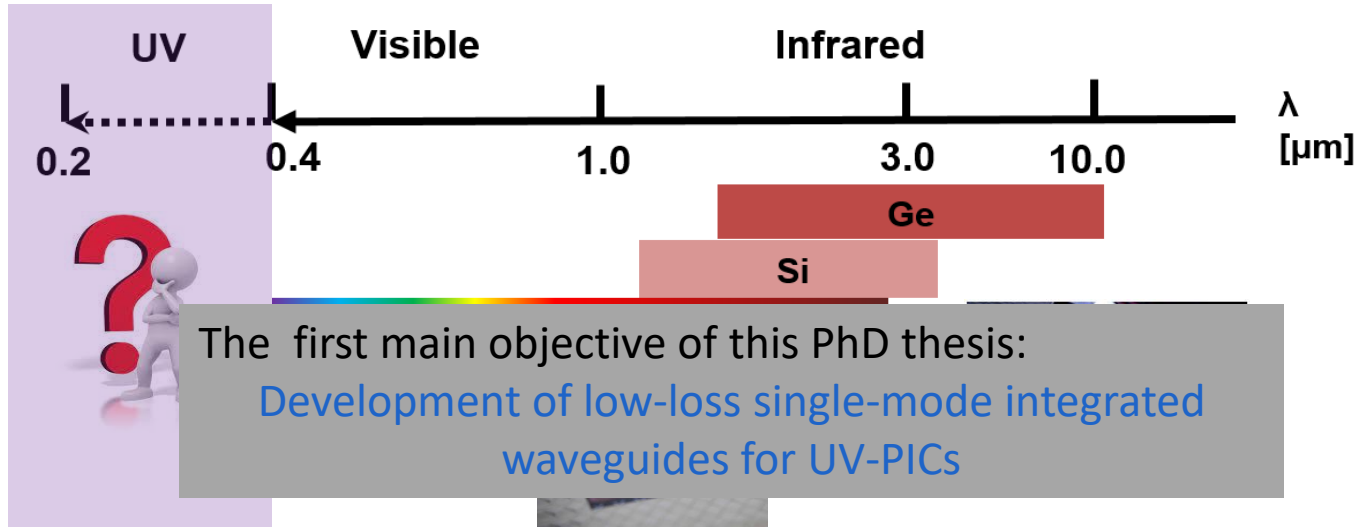


PIC



EIC

# CHALLENGES OF UV-PIC PLATFORM



- Strong absorption
- High scattering  $\propto \lambda^{-4}$

UV PHOTONIC INTEGRATED CIRCUITS FOR LABEL-FREE STRUCTURED ILLUMINATION MICROSCOPY AND QUANTITATIVE PHASE IMAGING

# SEEING THING BETTER WITH OPTICAL MICROSCOPY

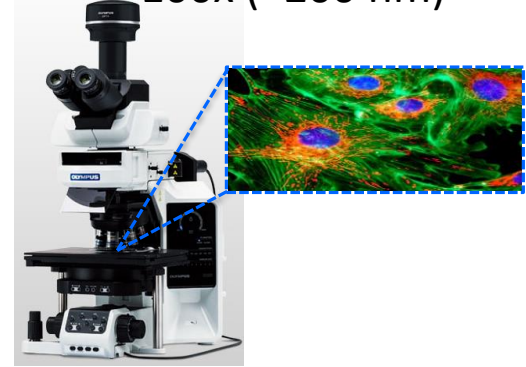
~3x (~0.1 mm)



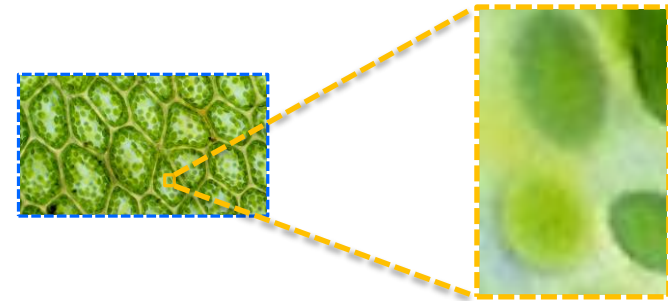
~10x (~1  $\mu\text{m}$ )



~100x (~200 nm)



See better with cascaded lenses?



Magnified but blurred

# WHAT DETERMINES THE RESOLUTION?



[https://en.wikipedia.org/wiki/Diffraction-limited\\_system](https://en.wikipedia.org/wiki/Diffraction-limited_system)

## Abbe's resolution limit

$$d = \frac{\lambda}{2n \sin(\theta)} = \frac{\lambda}{2NA}$$

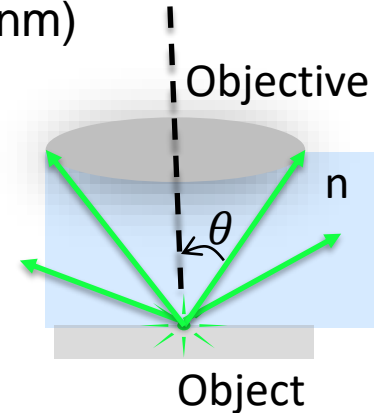
- Wavelength ( $\lambda$ )

Visible (400 nm-700 nm)

- Refractive index ( $n$ )

Air ( $\sim 1$ ), oil ( $\sim 1.55$ )

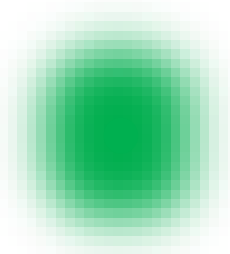
- Maximum angle ( $\theta$ )



# COMPARISON OF SUPER-RESOLUTION MICROSCOPY TECHNIQUES



Single fluorophore molecule (~nm)



Imaged fluorescence (~200 nm)

- Single molecular localization microscopy (SMLM)

- ✓ high resolution (~10 nm)

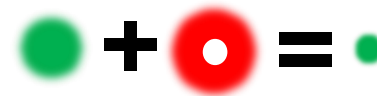
- ✗ Slow (~min), special fluorescent dye



- Stimulated emission depletion microscopy (STED)

- ✓ high resolution (~30 nm), fast (~s)

- ✗ High phototoxicity, complicated optical system



- Structured illumination microscopy (SIM)

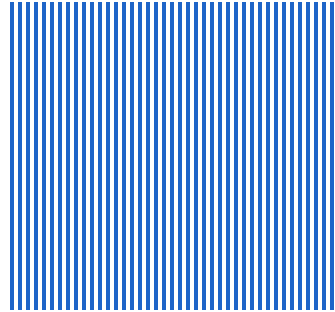
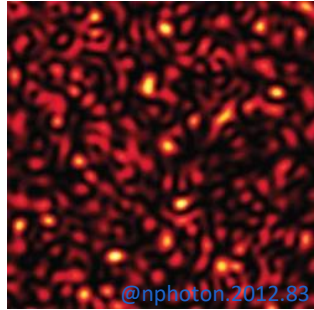
- ✓ Fast (~s), compatible with conventional dyes

- ✗ Relatively low resolution (~100 nm)

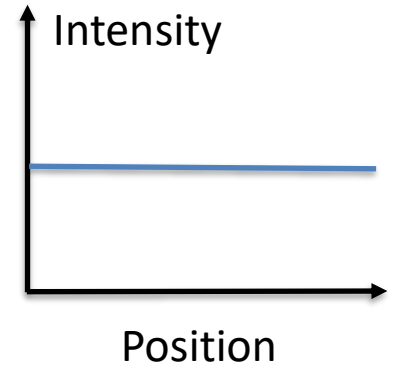
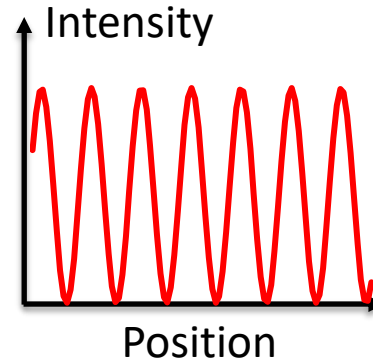
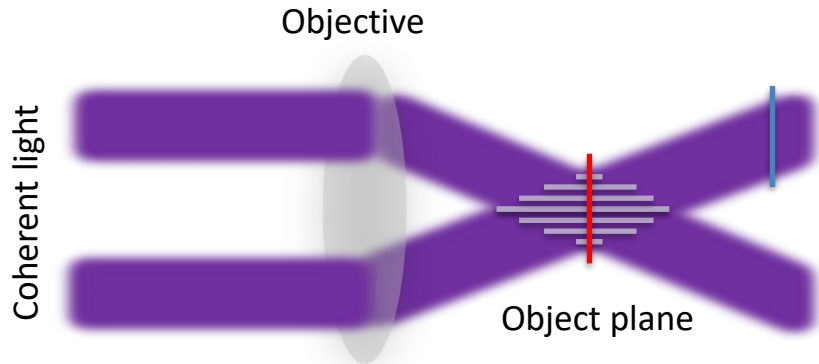


# WHAT IS STRUCTURED ILLUMINATION?

Speckles



Sinusoidal



Schematic of two-beam interference



# COMPACT, LOW-COST SOLUTION FOR SIM MICROSCOPES

Present SIM microscope configuration

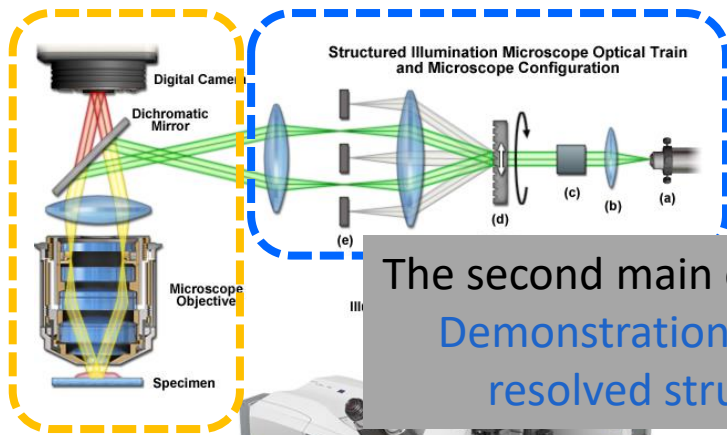
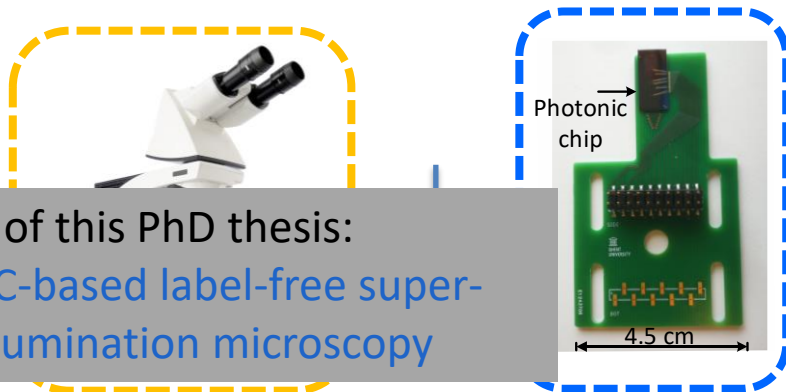


Figure 8



Our approach using UV-PIC



The second main objective of this PhD thesis:  
Demonstration of UV-PIC-based label-free super-resolved structured illumination microscopy

~5 cm x 5 cm



400 nm

700 nm



360 nm

200 nm

400 nm

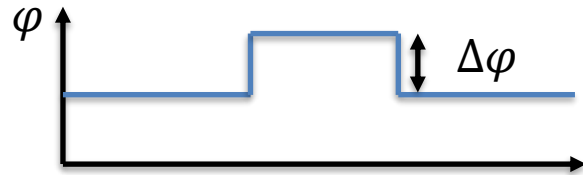
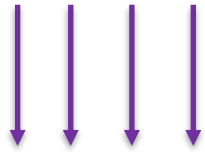
700 nm

[1] <https://zeiss-campus.magnet.fsu.edu/articles/superresolution/supersim.html>  
[2] C. Lin, et al., Nature Communications, 13(1), 4360 (2022)

UV PHOTONIC INTEGRATED CIRCUITS FOR LABEL-FREE STRUCTURED ILLUMINATION MICROSCOPY AND QUANTITATIVE PHASE IMAGING

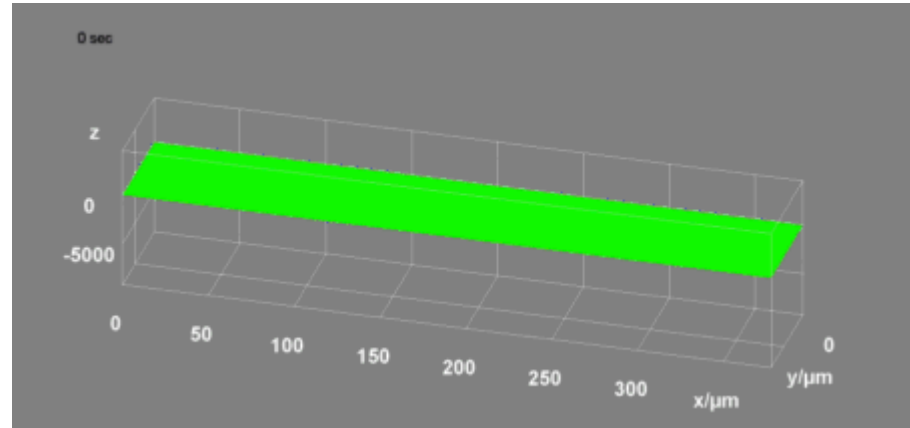
# WHAT IS PHASE OF LIGHT?

$$E(x) = Ae^{i\varphi(x)} = Ae^{i\left(\frac{2\pi}{\lambda}nx\right)}$$



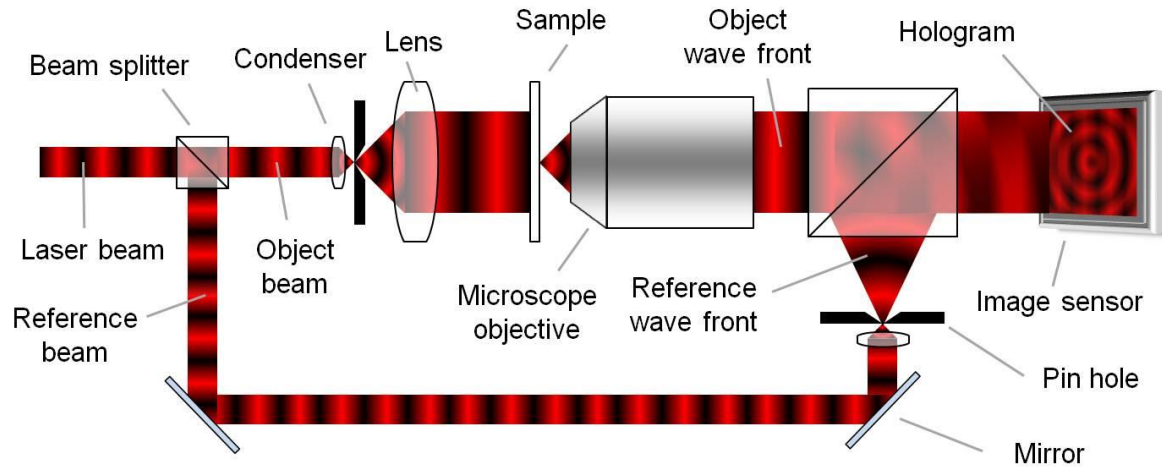
$$\Delta\varphi = \frac{2\pi h(n_2 - n_1)}{\lambda}$$

By knowing the refractive index ( $n$ ),  
we can deduce the thickness of the object ( $h$ ).



Height monitoring during etching

# INTERFEROMETRIC BASED QUANTITATIVE PHASE IMAGING



Phase noise

- Vibration
- Thermal drift

# ROBUST INTENSITY-BASED QUANTITATIVE PHASE IMAGING

## Kramers-Kronig relations (Hilbert transform)

$$Z_i = -\frac{1}{\pi} PV \int_{-\infty}^{+\infty} \frac{Z_r(X)}{(X-x)} dX$$

$$Z_r = \frac{1}{\pi} PV \int_{-\infty}^{+\infty} \frac{Z_i(X)}{(X-x)} dX$$

**Conditions:**

1: Causality:

2: Analyticity:

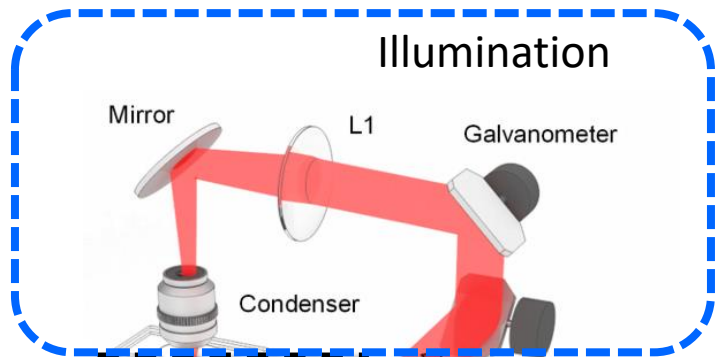
Complex field:  $E(x) = A \cdot e^{i(kx+\varphi)}$

Intermediate function  $\chi(x) = \ln(E(x)) = \ln(A) + i(kx + \varphi)$

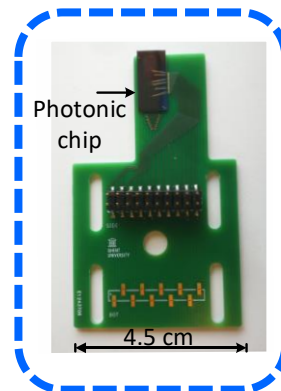
Imaginary:  $\chi_i = kx + \varphi$   $\longrightarrow$  Phase

Real:  $\chi_r = \ln(A)$   $\longrightarrow$  Amplitude

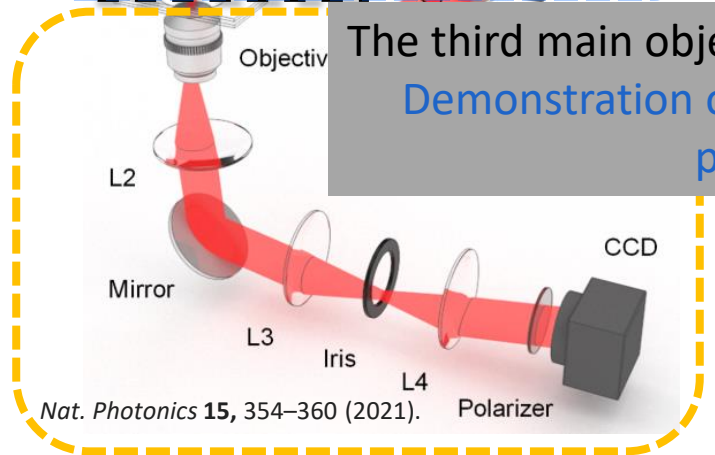
# COMPACT, LOW-COST SOLUTION FOR KK-BASED QPI



Our approach using UV-PIC



The third main objective of this PhD thesis:  
**Demonstration of UV-PIC-based quantitative phase imaging**



*Nat. Photonics* **15**, 354–360 (2021).

Configuration of the KK-based QPI technique



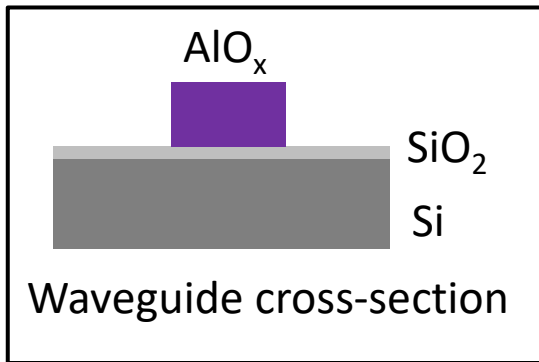
Low-loss single-mode integrated  
waveguides for a UV-PIC platform



# STRATEGIES TO PROCESS $AlO_x$ WAVEGUIDE

## Deposition

ALD- $AlO_x$  @150 °C →



High purity

ALD- $AlO_x$  @300 °C ←

## Etching

- **Etching rate**

Fluorine based → Chlorine based  
(3~4 nm/min → ~50 nm/min)

Nonvolatile  $AlF_3$  ↓  
volatile  $AlCl_3$  ↑

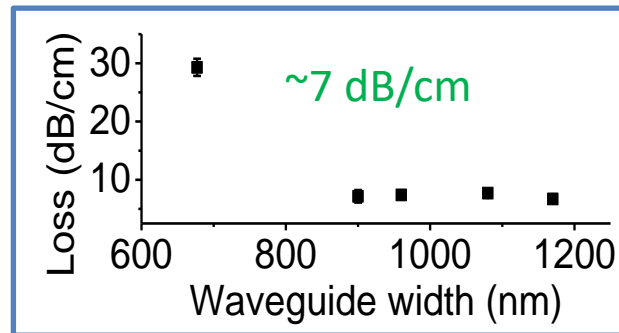
- **Etching selectivity**

Photoresist mask →  $SiN_x$  mask  
(~0.1 → ~1.5)

- **Etching quality**

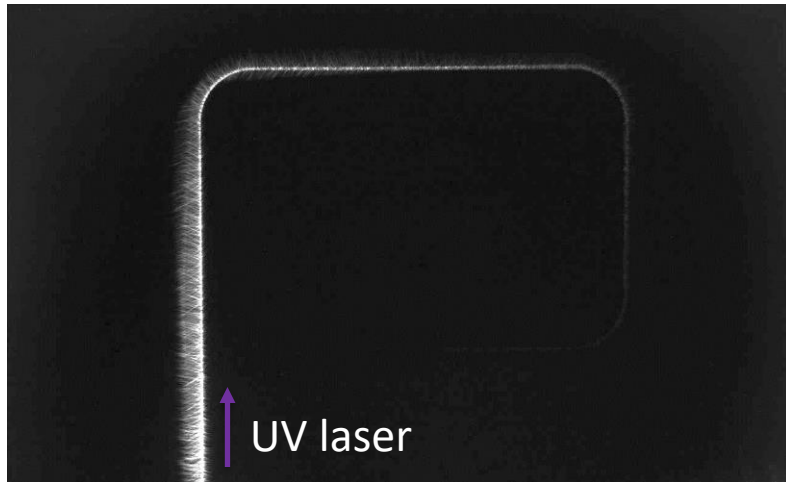
Gas mixture  $BCl_3$  →  $BCl_3/Cl_2/Ar$   
(loss)

$BO_x$  ↓  
 $BClO_x$  ↑

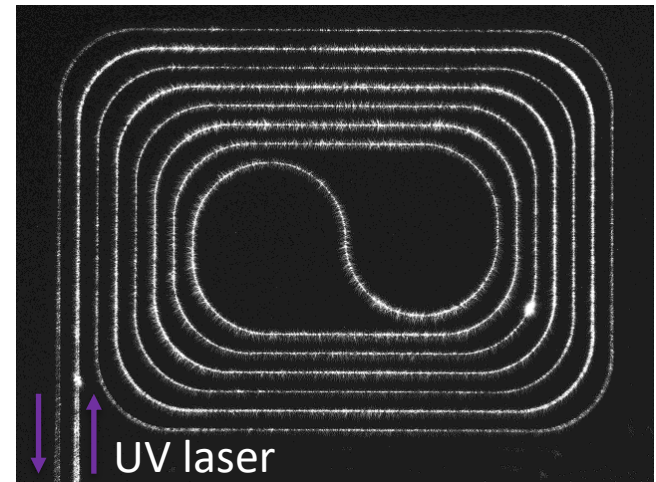


# CLEAR IMPROVEMENT OF WAVEGUIDE FABRICATION

UV light propagation in spiral waveguides with a total length of 2.7 cm

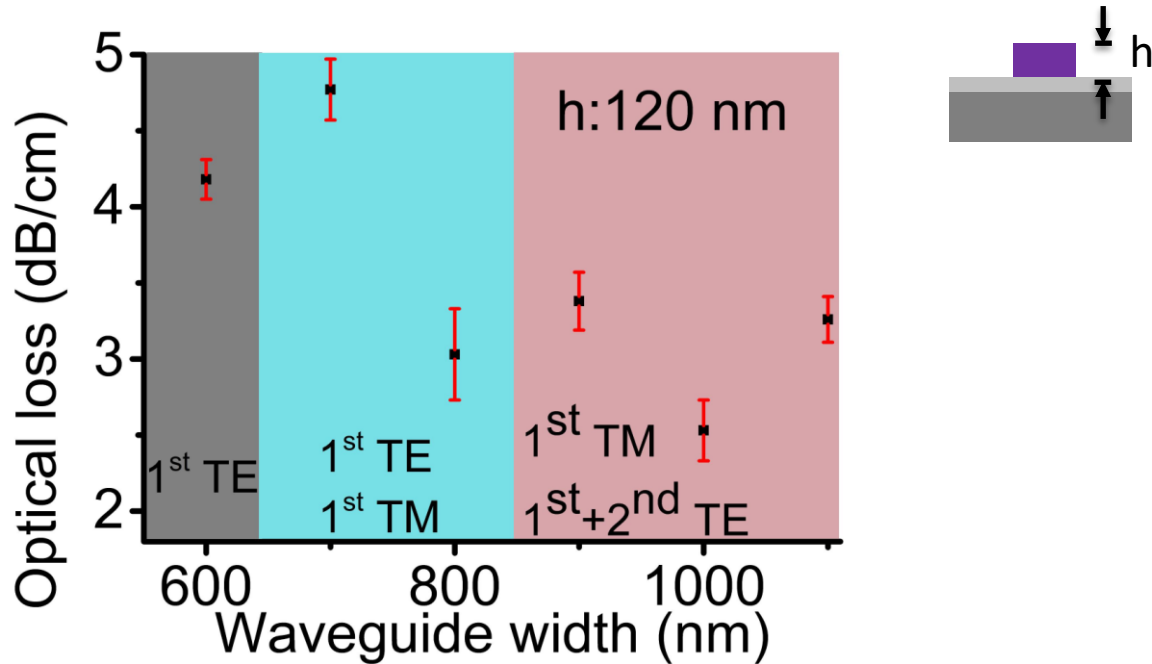


Before optimization



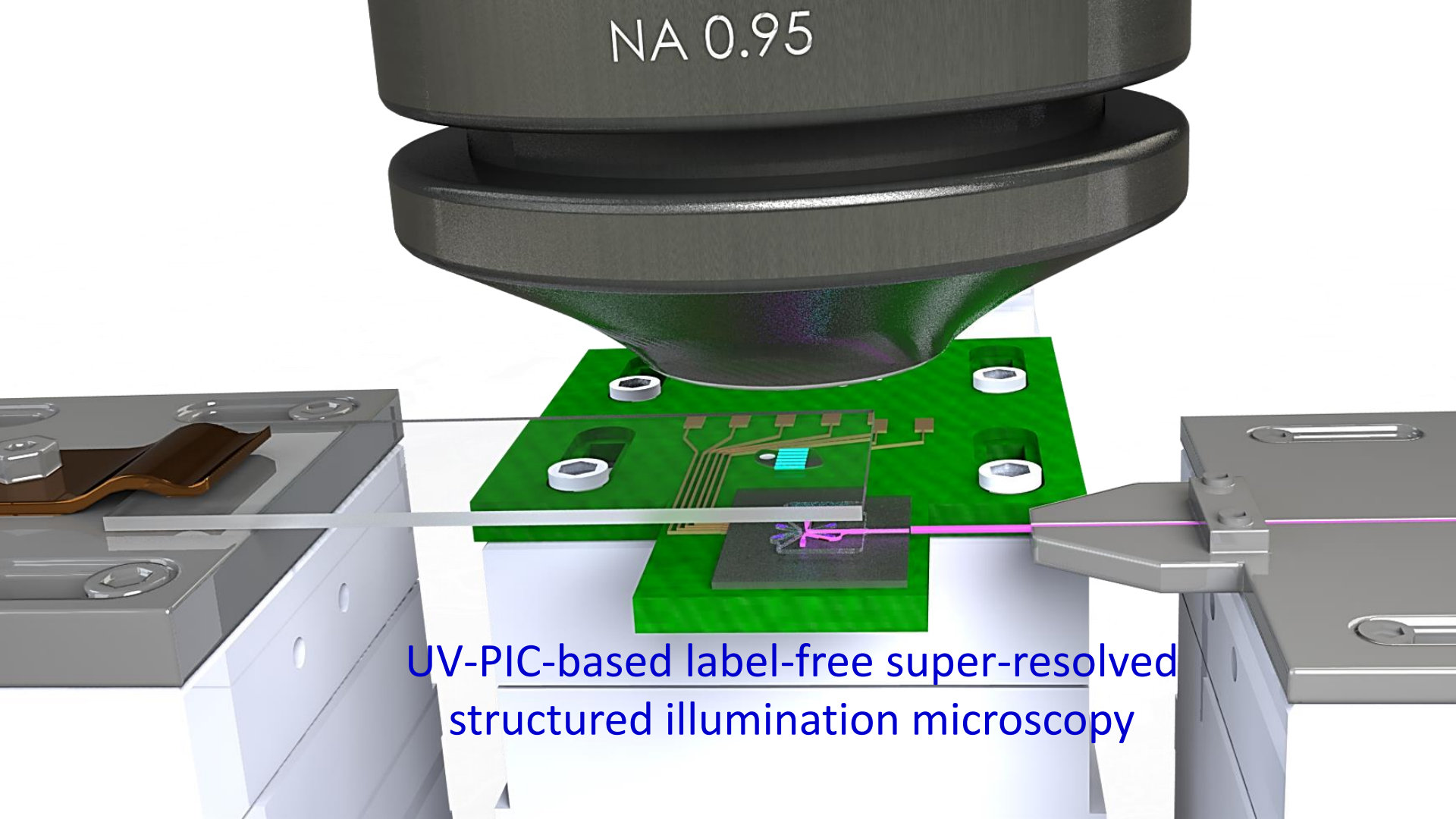
After optimization

# 3 dB/CM AT A WAVELENGTH OF 360 NM



Relationship between the waveguide width and waveguide loss

NA 0.95



UV-PIC-based label-free super-resolved  
structured illumination microscopy

# UNVEILING PRINCIPLE OF SIM WITH A UV PIC

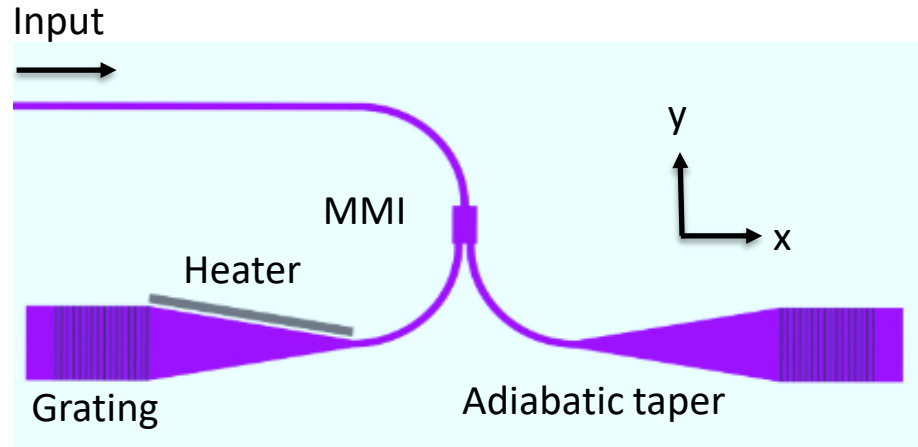
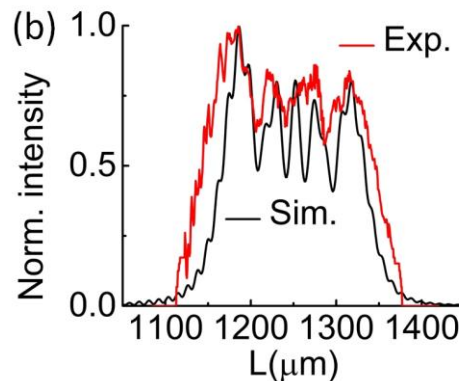
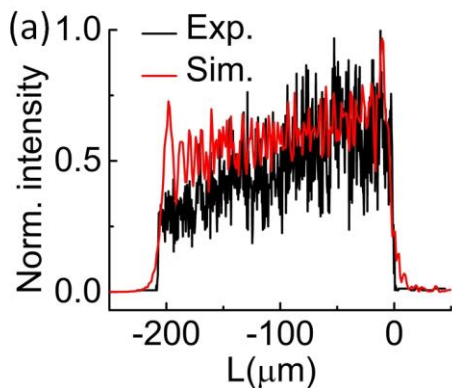
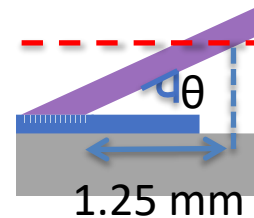
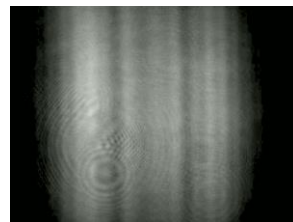
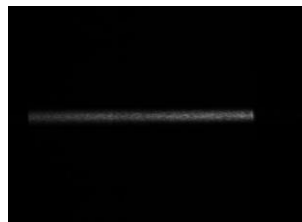
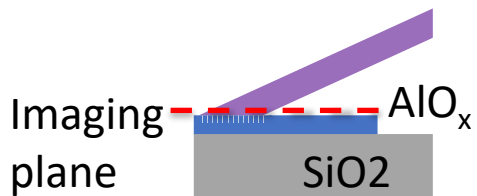


Diagram of UV-PIC for 1D structured illumination

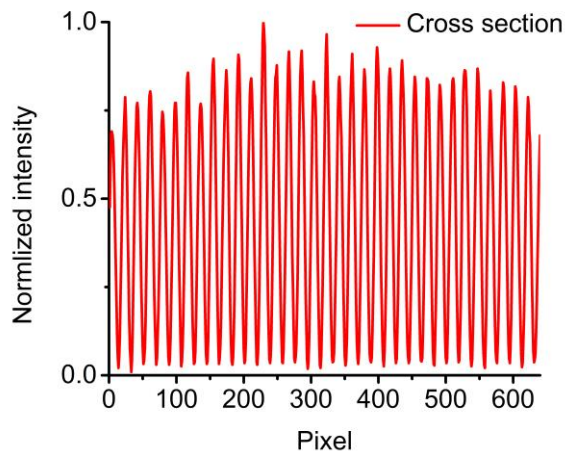
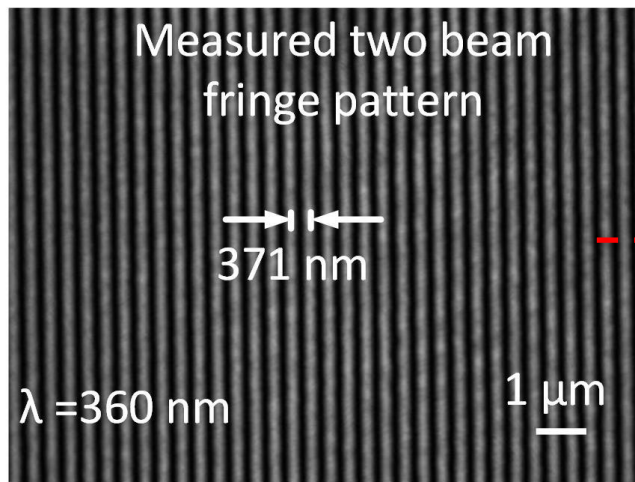
# UV BEAM WITH A LARGE FIELD OF VIEW

FOV  $170\ \mu\text{m} \times 200\ \mu\text{m}$



Beam profile at near field (left) and far field (right),  $\theta=11.7^\circ$

# HIGH VISIBILITY OF FRINGE PATTERN



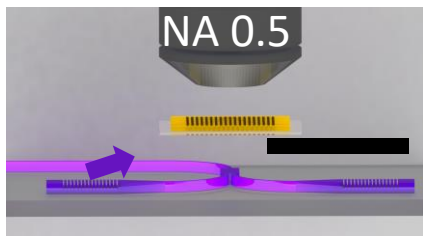
UV two beam interference fringe pattern,  $\theta = 29^\circ$

High Visibility up to 0.93



# DEMONSTRATION OF CHIP-SIM ON 1D OBJECT

Grating pitch  $G=300$  nm  $<$  optical resolution  $585$  nm

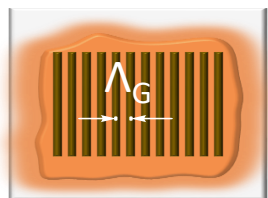
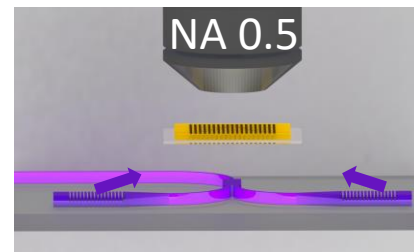
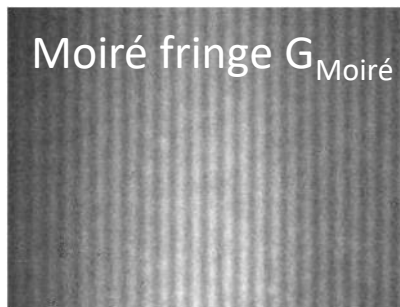


Real space

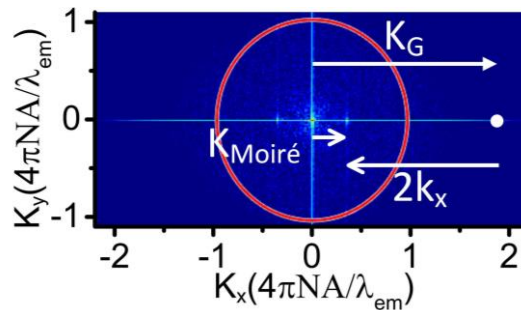
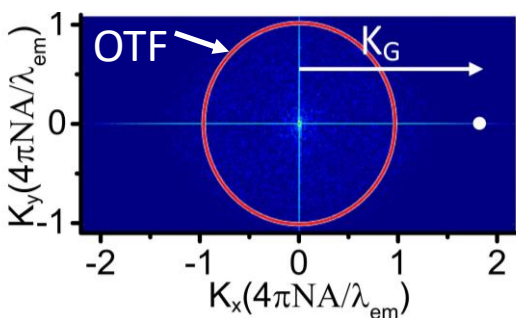
Uniform illumination



Structured illumination

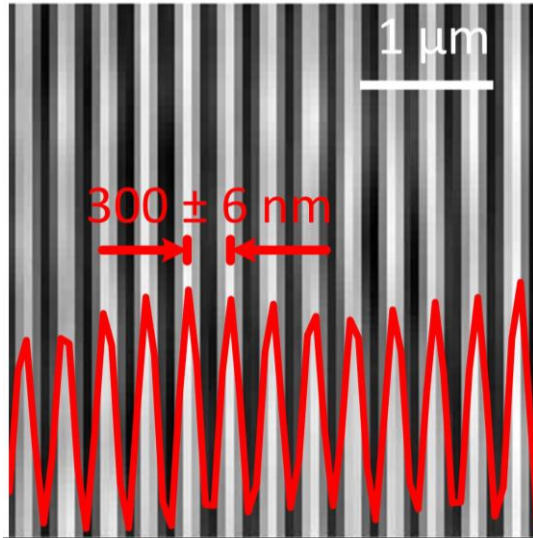


Fluorescent object

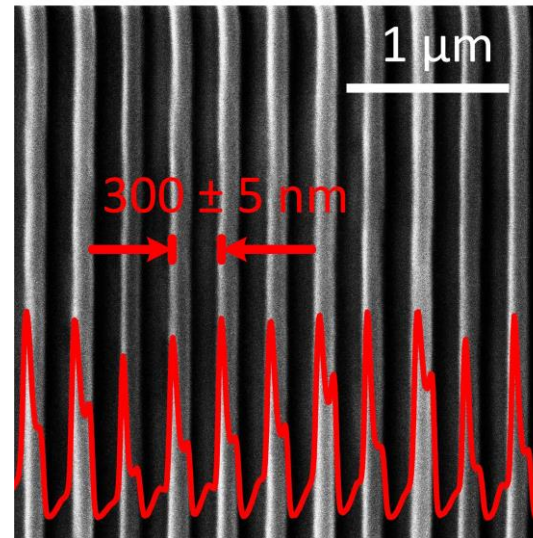


Fourier space

# RESOLUTION ENHANCEMENT CHECKED BY SEM



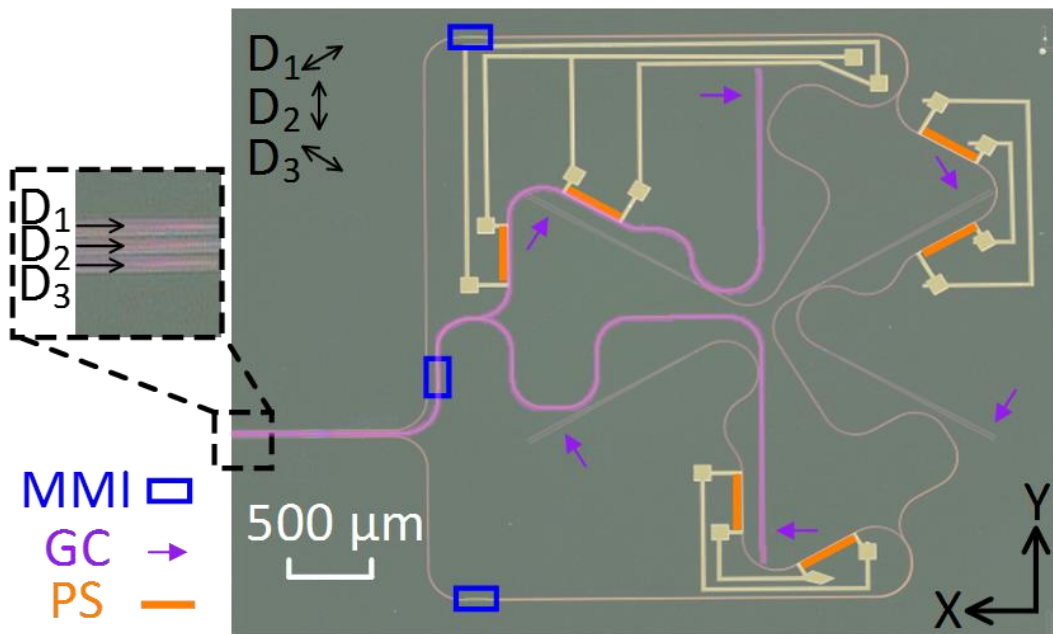
SIM image of dye  
filled groove



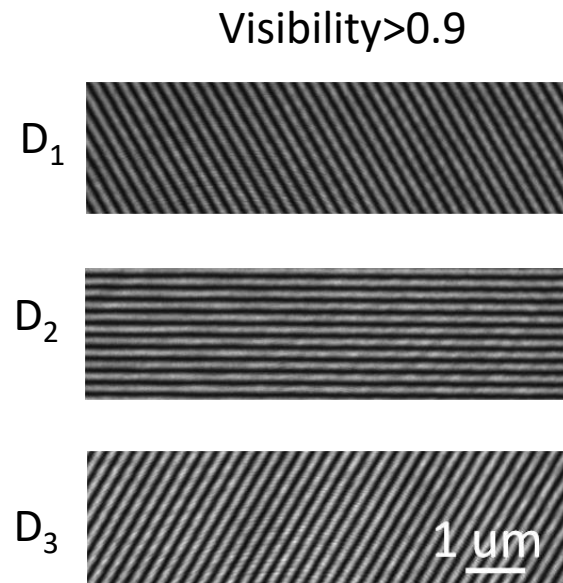
SEM image of metal lines

Super-resolution SIM using photonic chip is  
demonstrated on 1D object

# CIRCUITS DESIGN FOR STRUCTURED ILLUMINATION

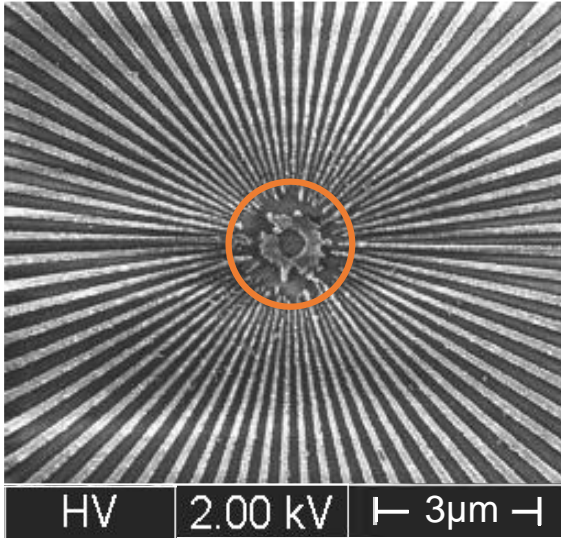


Optical image of the fabricated UV-PIC

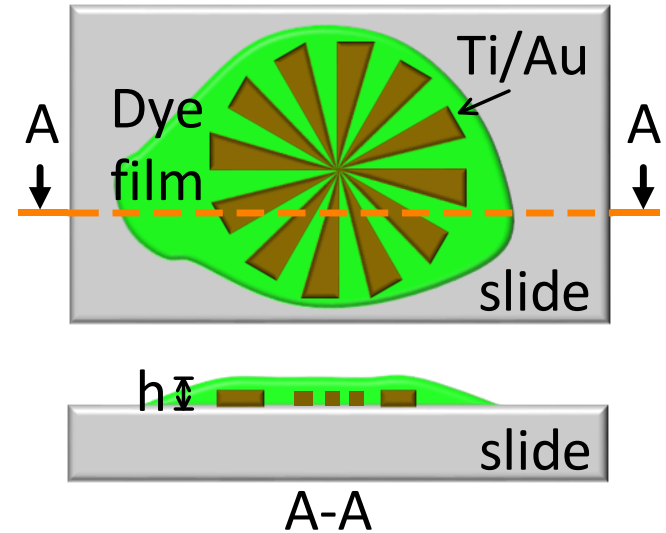


Optical images of the profiles of the generated structured illumination

# QUANTIFYING THE PERFORMANCE OF PIC-BASED SIM



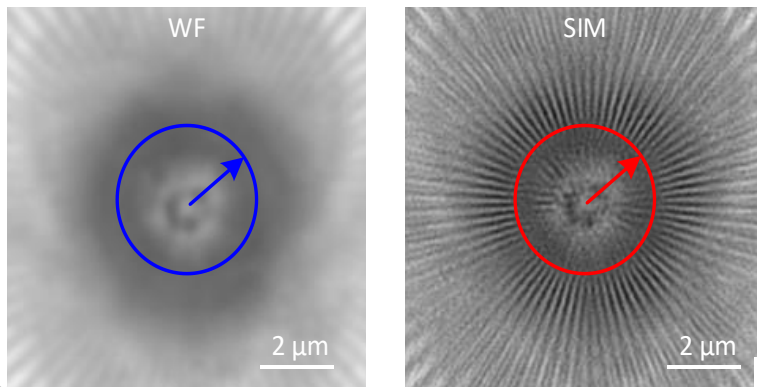
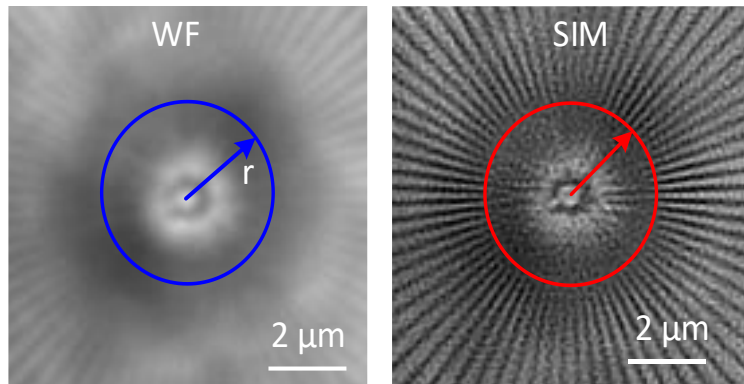
SEM image of metallic  
spoke target



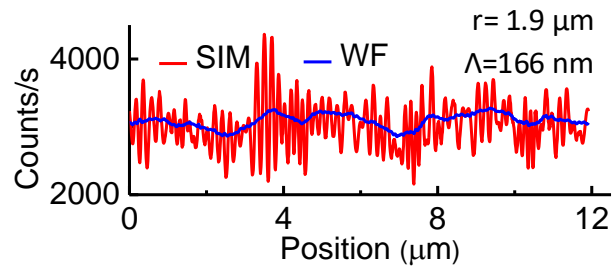
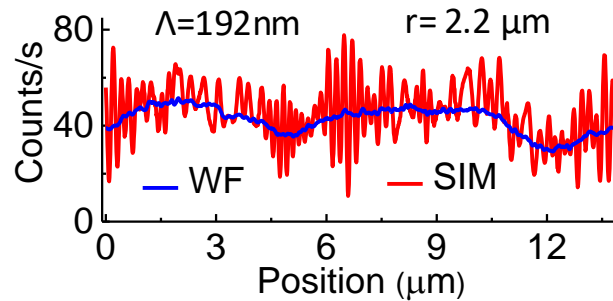
Schematic of fluorescent  
spoke target

# X1.8 TIMES BETTER WITH UV-PIC SIM

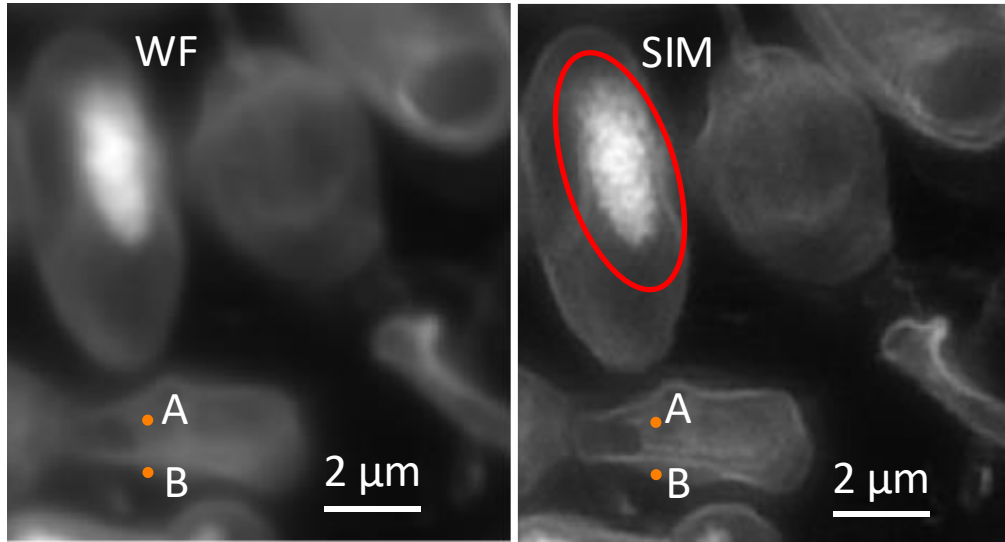
WF and SIM image of the spoke target



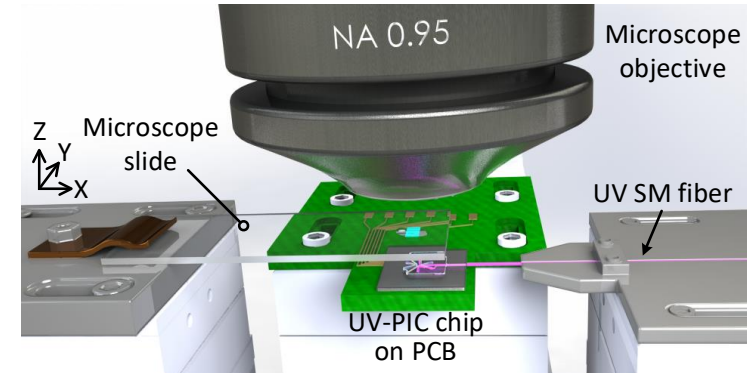
Intensity profile along the circle at  $r=1.9 \mu\text{m}$



# SUPER-RESOLVED AUTOFLUORESCENCE IMAGES OF YEAST CELLS



WF and SIM image of yeast cells

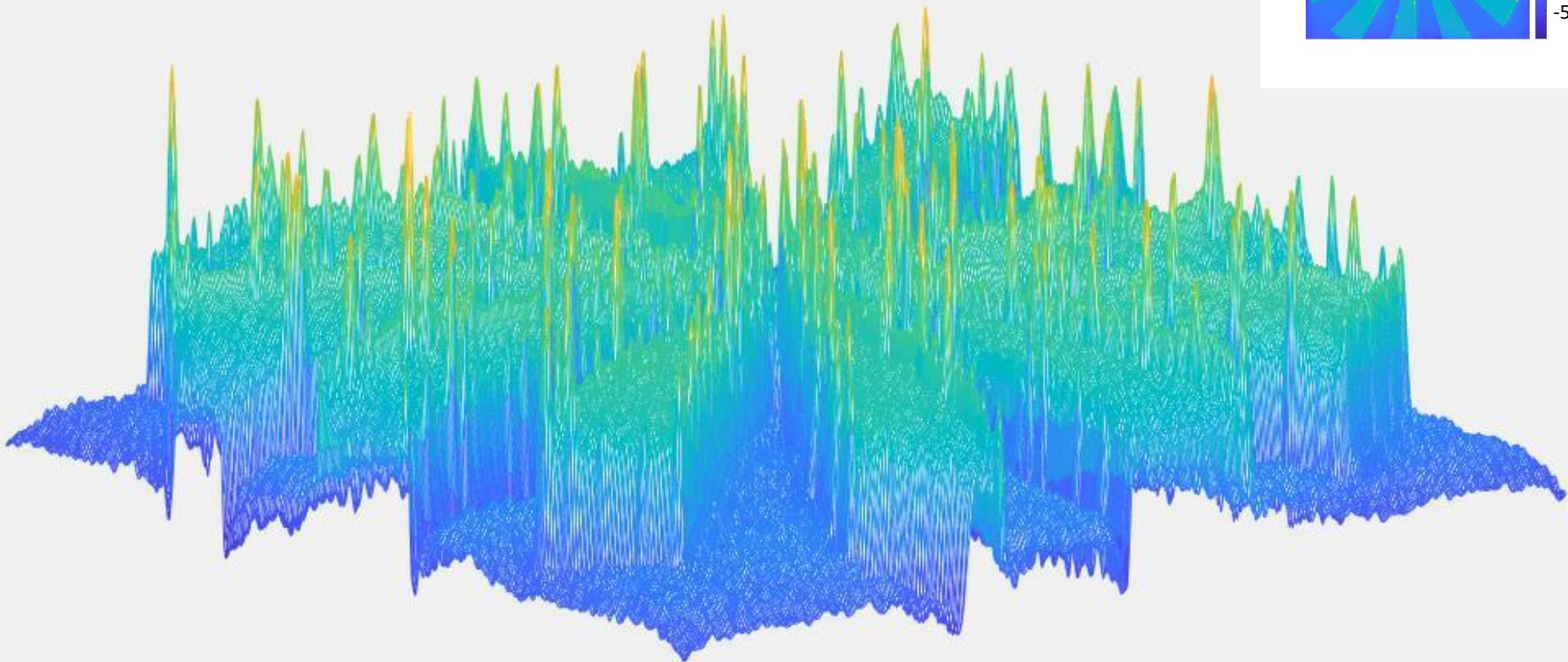
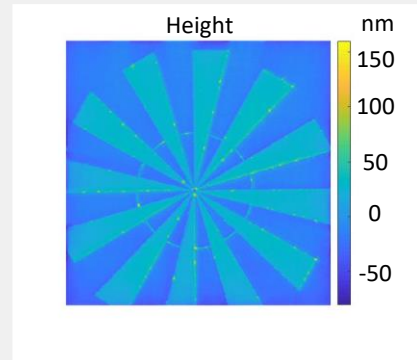


Schematic of the UV-PIC-based SIM technique

Enhancement factor: x1.6

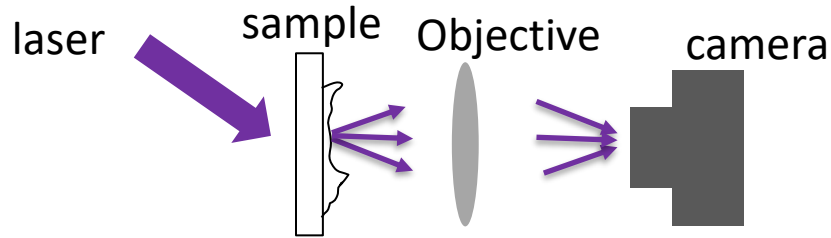


# UV-PIC-based quantitative phase imaging





# CONFIGURATION TO IMPLEMENT KK-RELATIONS



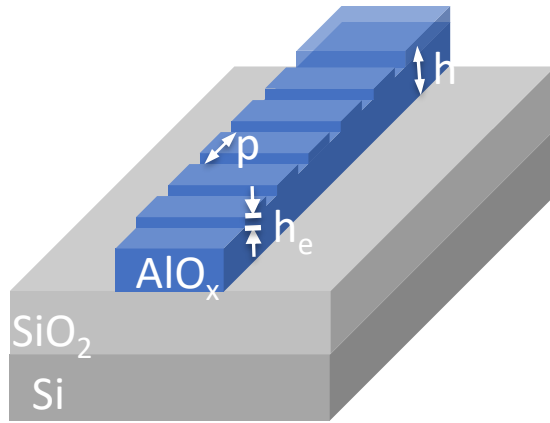
## Conditions:

- 1: Causality:
- 2: Analyticity:

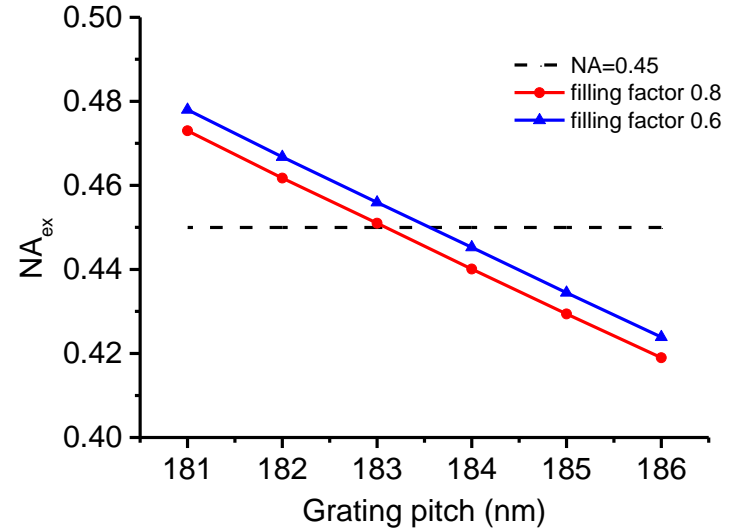
1. Vanish one of the half planes in k-space,  $NA_{ex} \geq NA_{co}$
2. Work in bright field condition,  $NA_{ex} \leq NA_{co}$

$$NA_{ex} = NA_{co}$$

# HIGH ACCURACY ON BEAM MANIPULATION VIA UV-PICs



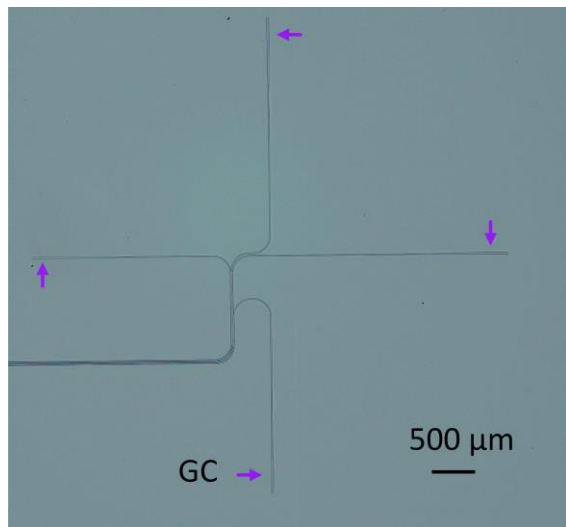
Schematic of grating out-coupler



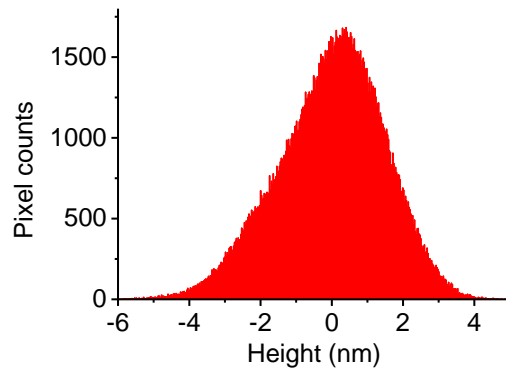
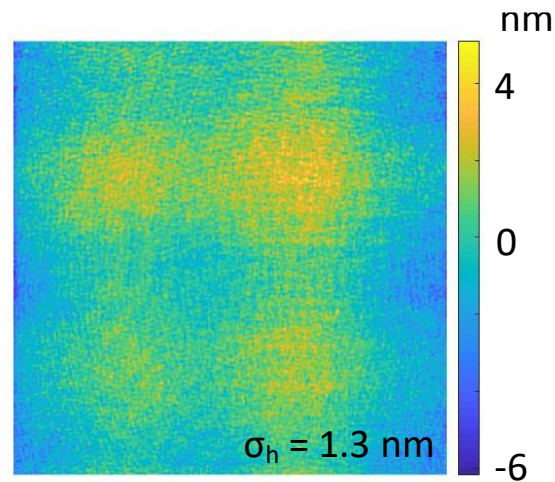
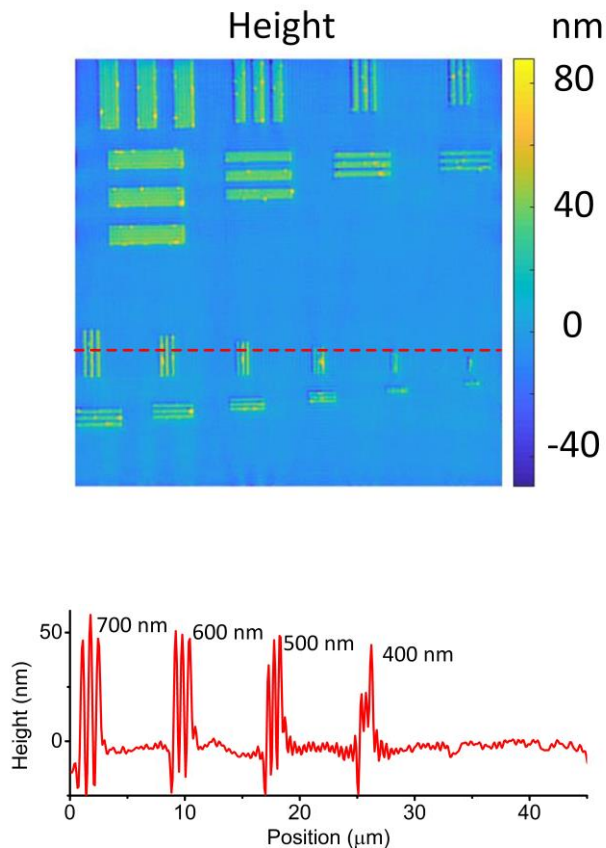
Relationship between numerical aperture  $NA_{ex}$  and grating pitch at filling factor of 0.8 and 0.6, respectively.

$$\Delta NA_{ex} = 0.005$$

# UV-PIC FOR QUANTITATIVE PHASE IMAGING



Optical image of fabricated UV-PIC for KK-QPI



# PROSPECTIVES

- Low spatial noise QPI using on-chip switching approach
- Large-field-of-view SIM (0.2 mm  $\rightarrow$  0.5 mm)
- UV-PICs for multi-modal advanced microscopy (SIM and QPI)
- $\text{AlO}_x/\text{SiN}_x$  hybrid platform operating for UV/Vis wavelengths

# Q&A

## Chupao Lin

PhD candidate

E Chupao.Lin@UGent.be

T



@PhotonicsUGent



@Chupao Lin



Chupao Lin

[www.photonics.intec.ugent.be](http://www.photonics.intec.ugent.be)